

Baikowski



Solution partner for FINE MINERALS

POLISHING SOLUTION CATALOG

FINE ALUMINA, SILICA, CERIA & DIAMOND SOLUTIONS



Optimized Powders & Slurries through Advanced Particle Engineering

> Your Solution Partner for Precision Polishing

Baikowski® provides superior intermediate and final polishing solutions for demanding industries. Our expertise is engineered to solve surface challenges across diverse applications such as:

- **Optics & Photonics**: clarity, haze control, defect suppression.
- **Power electronics & RF**: high removal rate on hard crystals while obtaining excellent surface finish.
- **Semiconductor / CMP**: planarity, selectivity, low defectivity.
- **Metallography**: clean cutting, corrosion control, easy post polish cleaning.
- Polymers & Coatings: gloss without orange peel.

> Our know how

- Particle engineering: controlled crystallinity (α/γ) , morphology, SSA, and tight PSDs to reduce scratch risk while maintaining removal rate.
- Advanced milling & dispersion: stable, water based systems, optimized pH and viscosity for pad flow and cleanliness.
- Formulation design: alumina, silica, ceria and diamond chemistries tailored to your substrate and step (rough \rightarrow finish / kiss).











- > The following highlights catalog provides a general overview of our powders and ready-to-use slurries in terms of abrasives, based on the substrate to be polished:
- Ceramics & crystals
- Metal
- Glass & plastics

PRODUCT DESIGN

- > For all your question on Baikowski high-quality polishing solutions and fine-tuning ability (media, viscosity, pH control and beyond...), contact us. We will custom optimize the polishing product to fit your specific application and process. With a uniform and controlled removal rate, our particles can reduce the time required to achieve the desired surface finish, enhancing the performance, reliability, and value of your final products.
- > We also offer support and guidance on polish test measurements using our advanced equipment, ensuring precise assessment of surface roughness, roughness average (Ra), and peak-to-valley (P-V) metrics to meet your specific requirements.





- 1- Specific Alumina, Silica & Ceria Polishing Slurries
- 2- Other Alumina Polishing Solutions: Baikalox® Slurries
- 3- Main Diamond Slurries
- 4- Alumina Baikalox® polishing Powders
- 5- Alumina Baikalox® Car Polish Powders
- 6- Main Polishing Pads

1. Specific Alumina, Silica, & Ceria Polishing Slurries

Ceramics & Crystals	Main		Attribute (Typical values)			
Substrates	Code	Al ₂ O ₃	SiO ₂	d ₅₀	рН	Other
	SPH-7	X		0.25	12-13	Felt Pad
	SPH-9D	X		0.30	12-13	
Sapphire (C-axis)	SPH-10	Х		0.30	12-13	
	SPH-9LA	Х		0.25	9	
	SPH-53		Х	0.10	9-10	
Sapphire (A/R-axis)	SPH-51		Х	0.10	9-10	
Alumina Nitrate / ALN	ALN-6L	Х		0.30	1-3	Low shedding - Felt Pad
Lithium Niobate / LT	SLT50		Х	0.05	2-4	
Lithium Niobate / LN	SLN-180		Х	0.10	9-11	
	S020		X	0.04	9	
SiC	SiC-70S	Х		0.3	2-3	
	SS070		Х	0.08	3-5	
Silicon	S083		X	0.1	9-11	
YAG	YG-1	Х		1.00	1-3	CR plate
Crystals	CR85SF	X		0.05	7-8	Agglomerate-free



Metal	Slurries			Attribute (Typical values)			
Substrates	Code	Al ₂ O ₃	SiO ₂	d ₅₀	рН	Other	
	AG3410	Х		1.00	1-3	Easy cleaning -PU pad	
Alumainum / Al	AG3402	Х		0.15	1-3	Easy cleaning - Suede Pad	
Aluminum / Al	AG3507	Х		0.25	1-3	Easy cleaning	
	S061		X	0.06	1-3		
Copper / Cu	ACU-30	Х		0.15	1-3	Easy cleaning - Urethane Pad	
Molybdenum / Mo	A120G	Х		0.10	3-5		
	AG-25L	Х		0.25	3-8		
Germanium	AG-32	Х		0.5	3-5		
Gold	SAU-10		Х	0.25	2-4	Urethane Pad	
Titanium	AT1-30L	Х		0.20	1-3		

Glass & Plastics	Slurries			Attribute (Typical values)			
Substrates	code	Al ₂ O ₃	SiO ₂	CeO ₂	d ₅₀	рН	Other
Blue Glass	BG-S0	X			0.25	10-12	
	BG-100F	X			0.15	10-12	
	CP20FK			Х	0.15	9-11	
Glass & lens	CP2370			Х	1.00	9-11	PU pad
	CP5N			Х	0.05	6-8	
Quartz	CP20S			Х	0.15	9-11	
	CP400			Х	0.30	9	
Polycarbonate	BL-700	X			0.70	1-3	

> The CP-series cerium-oxide—based slurries are formulated for final polishing of high-performance glass components. With a finer mean particle size and a tighter particle-size distribution than conventional ceria powders, they deliver better surface roughness on soft glass while reducing the risk of surface burn.



2. Other Alumina Polishing Solutions: Baikalox® Slurries

Main substrate tested	Polishing Slurries	Polishing step	*Nominal particle size (µm)	*рН	*Slurry density (g/cm³)	*PSD (μm) d ₅₀
Metal, crystals & ceramics	GE1S	Rough	3.0	7-8	1.2	13
Metal, crystals & ceramics	GE6S	Rough / Interme- diate	1.0	7-8	1.2	8.0
Metal, crystals & ceramics, varnish & lacquers	GE15S	Intermediate	0.3	7-8	1.2	4.5
Metal, crystals & ceramics, glass & lens	CR1S	Rough	3.0	7-8	1.2	1.0
Glass & lens, metal	CR6S	Rough / Interme- diate	1.0	7-8	1.2	0.5
Glass & lens	CR15S	Intermediate	0.3	7-8	1.2	0.2
Metal, glass & lens	CR30S	Finish	0.1	7-8	1.1	0.2
Glass & lens	CR85SF	Kiss polishing	0.05	7-8	1.1	-

^{*}Typical values

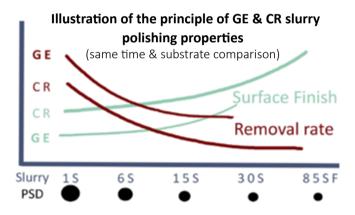
> Baikalox® ultra-pure alumina slurries are ideal for polishing applications where ease of use and material conservation are priorities.

Their formulations offer a stable suspension in a neutral, non-toxic base that remains moist on the lap or polishing pad, ensuring consistent performance.

For those who prefer, powders are also available.







- > In the Optic & Photonic fields, kiss polishing with our advanced solutions achieves the optical clarity required.
- > For metallographic polishing, Baikowski® fine alumina solutions on aluminum and copper reduce process time and offer easier cleaning than traditional colloidal silica products, while meeting strict requirements for microstructural analysis.



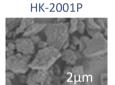
3. Main Diamond Polishing Slurries For SiC & GaN

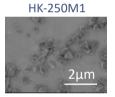
> For ultra hard ceramics and crystals (SiC, GaN) lapping and polishing, our diamond solutions offer exceptional removal rates and ultra smooth finishes (Ra < 0.6 nm). Custom powder formulations are available with particle sizes from 0.05 to 40 μm in various diamond types (Polycrystalline, Monocrystalline, Heat Treated and Surface Treated), and base liquid (water, emulsion, oil).

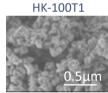
Polishing Slurries	Diamond Types	Liquid Base	*Nominal Particle Size μm
HK-250M1	Monocrystalline	ystalline Emulsion	
HK-100T1	Monocrystalline Heat Treated	Oil	0.10
HK-30P4A	Polycrystalline	Oil	0.03
HK-1000P1A	Polycrystalline	Oil	1
HK-SOOP1A	Polycrystalline	Oil	0.5
HK-2SOP1A	Polycrystalline	Oil	0.25

Polishing Slurries	Diamond Types	Liquid Base	*Nominal Particle Size μm
HK-2000P1	Polycrystalline	Water	2
H K-1000P1W	Polycrystalline Wate		1
HK- SOOP1 W	Polycrystalline	Water	0.5
HK-2SOP1W	Polycrystalline	Water	0.25
HK-100P1 W	Polycrystalline	Water	0.1
HK-SOP1W	Polycrystalline	Water	0.05
HK-30P1W	Polycrystalline	Water	0.03

*Typical values

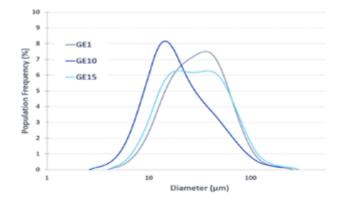






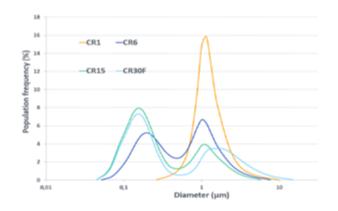
4. Alumina Baikalox® Polishing Powders

- > Our powders are controlled in:
- Particle size & particle size distribution (PSD)
- Chemical purity (3N, 4N and beyond)
- > Particle size distribution of the GE range



- Crystals & Crystalline phase
- Specific surface area (wide range of SSA available)
- Morphology

> Particle size distribution of the CR range





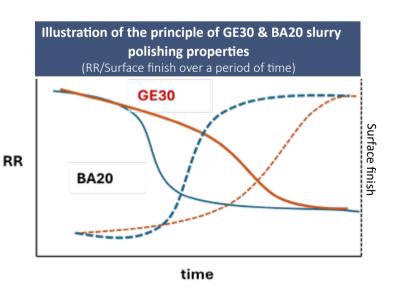
Main substrate tested	Polishing Powders	Polishing step	* Alpha content %	* SSP (m2/g)	* PSD (μm) d ₅₀
Metal, crystals & ceramics	GE1	Rough	100	< 3	13.5
Metal, Crystals & ceramics	GE6	Rough / Intermediate	100	5.2	8
Metal, crystals & ceramics, varnish & lacquers	GE15	Intermediate / Finish	90	14	5.5
Metal, varnish & lacquers	GE30	Intermediate	80	25	4.5
Glass & lens	BA105	Finish	8	97	2.5
Metal, glass & lens, crystals & ceramics	CR1	Rough	100	3	1.0
Glass & lens, metal	CR6	Rough / Intermediate	100	6	0.5
Soft lens, PMMA	CR10	Rough	100	7.1	0.2
Glass & lens	CR15	Intermediate	90	15	0.2
Metal, glass & lens	CR30F	Finish	80	26	0.2
Glass & lens	BRA105	Finish	7	100	1.0
Metal, Crystals & ceramics, including zirconia	PB12MAR	Finish	100	13	0.3

^{*}Typical values

4. Alumina Baikalox® Car Polish Powders

Polishing Powders	* Alpha content %	* SSP (m2/g)	* PSD (μm) d ₅₀
GE6	100	5.2	8
GE15	90	14	5.5
GE30	80	25	4.5
BA20	97	20	4.5
PB20CR	-	20	2.61
PB50CR	-	50	3.60





> For high end automotive applications, our alumina polishes deliver a high gloss, reflective finish.



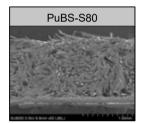
5. Main Polishing Pads

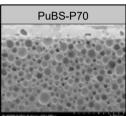
> Baikowski® offers a range of polishing pads

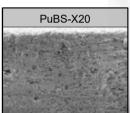
They are optimized for various applications, including metals, sapphire, other crystals and ceramics.

Each pad is designed to work seamlessly with Baikowski® specific polishing slurries, ensuring optimal performance. The recommended pad varies based on the desired roughness and flatness of the finished product. The list hereunder is partial. For personalized assistance with pad selection, please contact us.

SEM



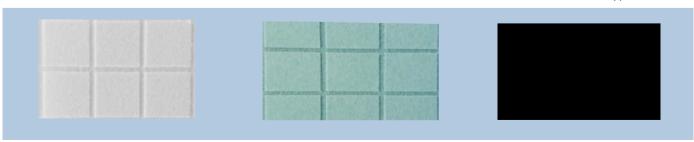






Polishing Pads	Applications	Туре	* Thickness (mm)	* Hardness ('') Asker A	Color
PuBS-S80	Sapphire C plane SiC, LN, LT, AIN	Non-woven	1.3	85	White
PuBS-P70	Sapphire C & A plane SiC, Metal	Polyurethane	1.3	75	White
PuBS-X20	Saphhire C plane	Non-woven	1.8	75	Sky blue
PuBS-K50	ISiC, Metal	Non-woven	2-5 (on request)	62	Gray
PuBS-W19	Metal, Glass	Suede	0.95	67	Black

*Typical values







Your solution partner for fine minerals



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